Notice of Allowability	10/664,179 Examiner	PLATZ
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Application No. Applicant(s)

20/004,179 PLATZER ET AL.	
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EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

Claim 20, line 2 replace "a" with - - an- - to correct a grammatical error.

Claim 26, line 1, replace "soluable" with - - soluble - - to correct typographical error.

REASONS FOR ALLOWANCE

- 2. The following is an examiner's statement of reasons for allowance: The claimed invention is drawn to the following:
 - 1. A method of making an imageable element comprising the steps of:
 - providing a substrate;

applying onto the surface of the substrate a photosensitive composition comprising:

a mixture of an aromatic diazonium salt containing compound having an alkoxy substituent and an aromatic diazonium salt containing compound free of an alkoxy substituent; and

treating the photosensitive composition to form a layer that adheres to the surface of the substrate.

The application is a continuation of U.S. SN 09/904,205, now U.S. Patent 6,638,679. The claimed invention is drawn to a method of making an imageable element having the steps of

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providing a substrate, applying and treating the photosensitive composition as recited above. The method is basically a coating method wherein the photosensitive layer is applied and treated to leave a photosensitive layer on a substrate. The inventive step is found in the photosensitive composition, which recites the mixture of an aromatic diazonium salt containing an alkoxy substituent and an aromatic diazonium salt containing a compound free of an alkoxy substituent. The parent case to 09/904,205 recites the following wherein claim 40 recites a method of producing an imaged element:

- 1. An imageable element selected from the group consisting of: a first and a second imageable element; said first imageable element comprising an imaging layer which comprises: a mixture of an aromatic diazonium salt containing compound having an alkoxy substituent and an aromatic diazonium salt containing compound of free of an alkoxy substituent; a polyvinyl acetal binder; and a sheet substrate; and
- said second imageable element comprising an imaging layer which comprises: a mixture of an aromatic diazonium salt containing compound having an alkoxy substituent and an aromatic diazonium salt containing compound free of an alkoxy substituent and a sheet substrate; wherein said imaging layer comprises a total aromatic diazonium salt containing compound content of at least 10 weight percent; and wherein the molar ratio of said aromatic diazonium salt containing compound having an alkoxy substituent to said aromatic diazonium salt containing compound that is free of an alkoxy substituent is from about 1.0:1 to 70:1.

The differences between the claims are to <u>making a imageable</u> element to <u>producing an imaged element</u>. One is a process for making an element to be used and the other is a process of using a previously formed element. Because of this distinction, the claims are not seen as rejectable over the judicially created doctrine of obviousness-type double patenting.

Prior art previous cited include the following:

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WALLS et al discloses a photosensitive element comprising a diazonium resin and a polyvinyl acetal resin wherein in column 3, lines 55-et seq. WALLS et al discloses that two or more of the diazotized structures are reacted with a paraformal dehyde to give two types of diazonium salts in the composition. WALLS et al lacks the use of two different diazonium resins in an explicit example in a mixture of an aromatic diazonium salt containing compound having an alkoxy substituent and an aromatic diazonium salt containing compound free of an alkoxy substituent.

AOSHIMA et al discloses a negative working recording material comprising an acrylic resin, a diazo compound and carbon black. The diazo compound having two or more diazonio groups on the polymer. This fails to meet or anticipate the claimed mixture of the aromatic diazonium salt containing compound having an alkoxy substituent and the aromatic diazonium salt containing compound free of an alkoxy substituent.

VERMEERSCH et al discloses a diazo-based element having improved storage stability comprises at least one diazo resin or diazonium salt containing as a substituent an alkyl or alkoxy group. This reference also fails to disclose the claimed imageable element having the mixture of the aforementioned diazonium resins.

Because none of the prior art references of record disclose the recited method, claims 1-27 are seen as allowable and passed to issue.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

3. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Examiner Chu whose telephone number is (571) 272-1329. The examiner can normally be reached on Monday - Friday from 9:30 am to 6:00 pm.

The fax phone number for the USPTO is (703) 872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the Group receptionist whose telephone number is (571) 272-1700.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PMR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

John S. Chu

Primary Examiner, Group 1700

J.Chu November 15, 2004